

**AMENDMENTS TO THE CLAIMS**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

1. (Currently amended) A method for the removal of metal impurities in chloride-based copper recovery processes, comprising contacting an aqueous strong chloride solution of monovalent copper with a chelating ion-exchange resin and removing the metal impurities from a strong chloride said solution of monovalent copper having an alkali chloride content of at least 200 g/l and a monovalent copper content of 30—100 g/l using said chelating ion-exchange resin resins.
2. (previously presented) A method according to claim 1, wherein there is a styrene-divinylbenzene matrix ring structure in the ion-exchange resin.
3. (previously presented) A method according to claim 1, wherein the functional group of the ion-exchange resin is the iminodiacetic acid group.
4. (previously presented) A method according to claim 1, wherein the functional group of the ion-exchange resin is the aminophosphonic group.
5. (previously presented) A method according to claim 1, wherein the metal impurity is zinc, nickel, lead, iron or manganese.
6. (cancelled)
7. (cancelled)
8. (previously presented) A method according to claim 1, wherein the removal of metal impurities is carried out in an acidic environment.

9. (previously presented) A method according to claim 1, wherein the removal of metal impurities is carried out in a neutral environment.
10. (previously presented) A method according to claim 1, wherein the copper-containing chloride solution that is the mother liquor in the resin is displaced before elution with an NaCl solution and that the alkaline solution to be used for regenerating the resin is displaced with an NaCl solution before the copper-containing chloride solution is fed into the resin.
11. (previously presented) A method according to claim 1, wherein the majority of the metal impurities in the strong chloride solution of monovalent copper are removed by hydroxide precipitation and the rest by using ion exchange.
12. (previously presented) A method according to claim 11, wherein the metal impurities are removed by hydroxide precipitation to a content of 0.1 - 1 g/l, after which the final purification is made using ion exchange.
13. (currently amended) A method according to claim 1, wherein said impurities are removed from ~~a strong chloride~~ said solution of copper by ion exchange at least to a level that corresponds to cathode copper LME-A grade impurity level.
14. (new) A method according to claim 1, wherein the alkali chloride content of said strong chloride solution is at least 200 g/l.
15. (new) A method according to claim 1, wherein the monovalent copper content of said strong chloride solution is 30 – 100 g/l.